

IN THE ABSTRACT:

Please cancel the current abstract and insert the following.

-- An exposure apparatus for exposing a wafer to light via a mask. The apparatus includes a process chamber in which the wafer is exposed to the light, a load-lock chamber connected to the process chamber via a gate valve, a transfer mechanism to transfer the wafer from another apparatus different from the exposure apparatus into the load-lock chamber, a booth which is connected to the load-lock chamber via a gate valve and covers the transfer mechanism, and a gas flow forming mechanism which includes a filter and causes gas through the filter to flow through the booth. --